

研究简报

高精度30kV高压稳压电源的研制

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摘要

本文介绍了为新型电子束曝光机研制的高精度30kV高压稳压电源。该电源采用双闭环调整,集中补偿和分散补偿相结合的设计方案。对电源的关键性技术采取了有力措施,使各项技术指标均达到设计要求。

关键词 [高压稳压电源](#) [高精度](#) [高稳定性](#)

分类号

DEVELOPMENT OF HIGH-PRECISION REGULATED POWER SUPPLY WITH 30kV HIGH VOLTAGE

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Abstract

A high-precision regulated power supply for a new type electron beam lithography system with 30 kV high voltage is recommended. The design scheme of double closed loop regulation and the design scheme of centralized compensation combined with dispersed compensation are adopted. In accordance with the technical requirements of regulated power supply, some key techniques have been properly handled. All its qualifications satisfy or exceed the original design requirements.

Key words [High voltage regulated power supply](#) [High-precision](#) [High stability](#)

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